A POWER SWITCHING IONIZATION PROFILE MONITOR (3D-IPM).

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Introduction

Conventional Set Up

New Design

The FLASH laser beam has a variable wavelength from 4.1 to 45 nm, and is located in an Ultra High Vacuum (UHV) beam pipe. Despite the vacuum a certain amount of residual gases still



- > **unification** of the horizontal an vertical monitors
- to ensure an optimal homogenous electric field
- compact design permits low voltage (U_max = 800 V)
- - > easier to handle & manufacture



Design Description

New Design

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FEM ANALYSIS

- Unification of the separate horizontal and vertical monitors with an alternating homogeneous electric field.
- A special cage protects the area of interest from electrical stray fields to ensure an optimal homogenous electric field.
- Decreasing the size of the device to 203 mm x 218 mm x 246 mm while at the same time reducing the applied electrical voltage with the appropriate low cost feedthroughs.
- With the Finite Element Method (FEM) a comparison of different residual gas particles is performed concerning their trajectories in the electric field.
- This procedure offers an optimization of the design by simulating the trajectory of the particles in the electrical field



supportsupportsupportsupportsupportplane 1 plane 4 plane 5 plane 3 plane 2 U = 800 V U = 705 V U = 500 V U = 295 V U = 200 V



with the deflection caused by the inhomogeneity of the field. Varying the CAD monitor model helps finding out the best possible determination of the laser beam position.

Device Specifications

• 2x grid bonded in a ring washer by Precision Eforming

➢ MN49 bonded to 20mm SS Frame

- a pulse generator for generating an alternating orthogonal electrical field
 - > A-GBS-MATRIXPULS 1x25 by GBS ELEKTRONIK GmbH ➢ with a frequency of 100 kHz [8]
- 2x micro-channel-plate and P47 phosphor screen assembly by HAMAMATSU
 - ➢ F2222-27P227 [4] Emission range 375 - 600 nm

Optical Limits of Measurements

The chosen parts leads to a signal intensity of 48,11% because of unavoidable transmission and response losses. The lower table shows the relative spectral emission, transmission and spectral response of the chosen parts and the optical system.

]	Phosphor-	Inspection	Objektive	Camera	relative Light-
		<u>screen</u>	Glass	Schneider	Basler	absorption
	H	Iamamatsu	Vacom	Kreuznach	acA2500-14gm	with Makro-
	F2	2222-27P227	VPCF40DUVQ-	Makro-Symmar		Symmar and
			L-BBAR2	5.8/80		AcA2500-14gm
wave-	r	el. spectral	rel.	rel.	rel. spectral	rel. trans-
lengh		emission	transmission	transmission	response	mission of light
in nm		in 1	in 1	in 1	in 1	relating 25 nm
3	50	0,00	0,90	0,00	0,00	0,00
3	75	0,10	0,90	0,66	0,00	0,00
4	-00	0,70	0,90	0,85	0,48	6,43
4	25	0,95	0,90	0,95	0,56	11,37
4	50	0,95	0,90	0,95	0,60	12,18
4	75	0,80	0,90	0,96	0,61	10,54
5	500	0,70	0,90	0,97	0,61	9,32
5	525	0,55	0,90	0,97	0,60	7,20
5	50	0,35	0,90	0,97	0,58	4,43
5	575	0,22	0,90	0,97	0,55	2,64
6	500	0.12	0.90	0.97	0.50	1.31



Simulation studies performed with the ANSYS 14.5 workbench module package proved the potential ratios, as can be seen in the upper Figure, to be optimal for a homogeneous electric field and hence for a straight flight of particles. Since the MCP has a diameter of merely 20 mm, only in the marked "area of interest" the electric field must be homogeneous. Also, the expected beam variation in X or Y is below ± 5 mm. Homogeneity in a larger space does not result in a higher spatial resolution.

Conclusion

The first prototype of a 3D-IPM is currently under construction and will be completed and tested in 2014. Before any test with a toggling electrical field, there will be tests with a rigid field. First practice tests are planned in 2015 at FLASH in DESY Hamburg site.

The special cage is visualized in the Figure below.





Temporal Resolution

The selected camera offers a shutter frequency of 12 pictures. This means that 12 times per second the position and the profile of the beam can be measured. The time between the horizontal and the vertical measurements of the profile is limited to the time of fly of the ions and the intensity of light of the screen. A N^{2+} lon needs 1 μ s from the middle of the assembly to the screen. The intensity of the light is unknown and it has to be tested. Certainly, the shutter time is much longer than the time of fly. But a shutter time of 400 μ s is realistic, resulting in a complete profile measurement of the beam every Millisecond.



203 x 218 x 246 mm mm for 3D-measuring